# Supporting Information for:

# Bilayer Quantum Hall States in an n-type Wide Tellurium Quantum Wells

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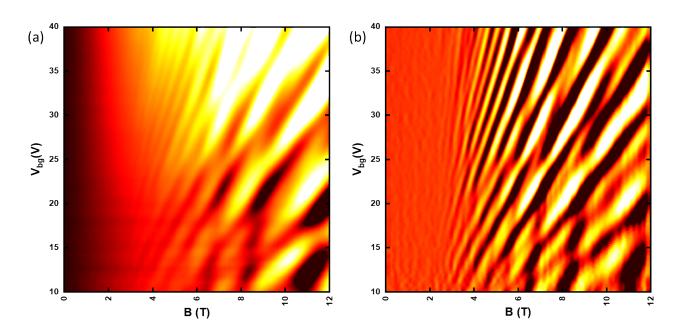
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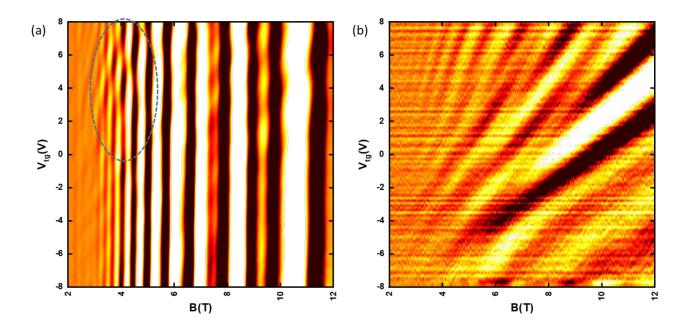
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### 1. Original and second derivative Landau level mapping



**Figure S1** Back gate voltage and magnetic field mapping of longitudinal resistance at 5K and  $V_{tg}$ =0V. The bright areas are resistance maxima which are crossing points formed by top and bottom layer Landau levels. (a) Original data ( $R_{xx}$ ) mapping. (b) The second derivative of  $R_{xx}$  with respect to B field ( $-\partial^2 R_{xx}/\partial B^2$ ) mapping shows the same information with more clarity compared to original data ( $R_{xx}$ ).

#### 2. Landau level hybridization between top and bottom layer 2DEGs



**Figure S2** (a) Top gate and magnetic field mapping of the second derivative of  $R_{xx}$  with respect to magnetic field  $(-\partial^2 R_{xx}/\partial B^2)$ . (b) Top gate and magnetic field mapping of the second derivative of  $R_{xx}$  with respect to top gate voltage  $(-\partial^2 R_{xx}/\partial V_{tg}^2)$ . The bottom layer Landau level distortion (circled in blue) can be explained by the interaction between top layer and bottom layer.

Figure S2(a) and (b) shows the quantum oscillation of Landau levels from bottom and top layer 2DEGs respectively. Landau level crossing features are clearly seen in the blue circle area. By comparing the Landau level sequences between top and bottom layer we can conclude that the crossing features are originated from the interaction between quantum oscillations.

# 3. Magnetic field B dependence of bilayer quantum oscillations

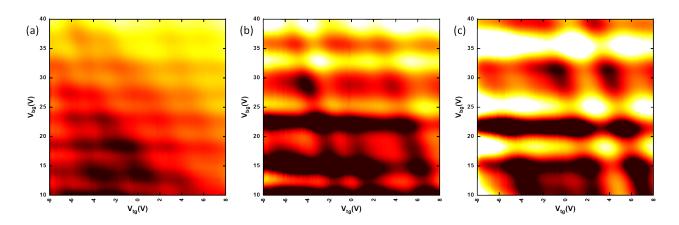


Figure S3: Top gate voltage and back gate voltage mapping of Rxx at different magnetic field: (a) 6T (b) 9T (c) 12T. The temperature is 8K.

# 4. Top gate dependence of bottom layer Landau level mapping

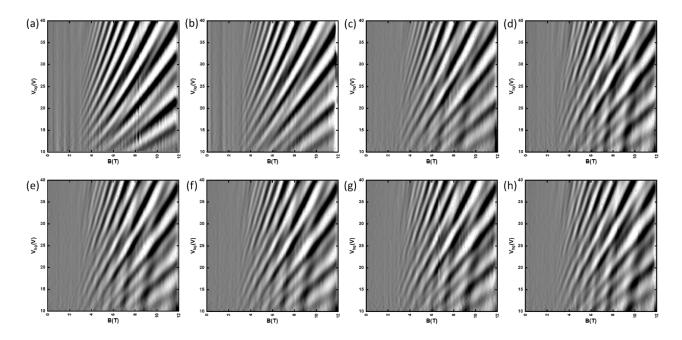
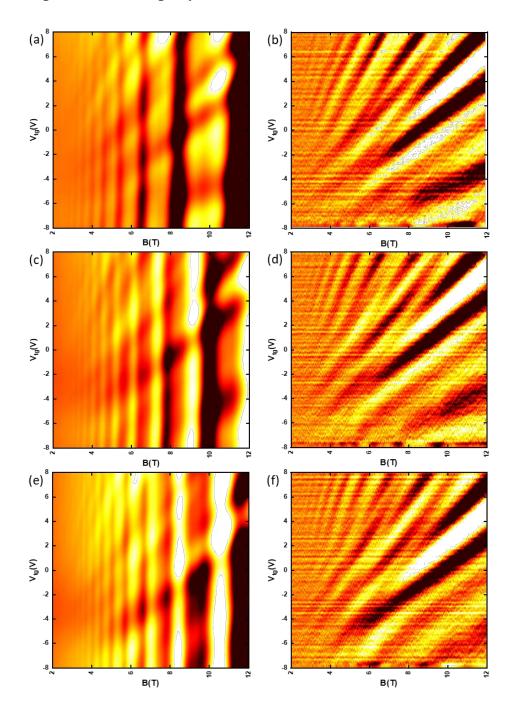


Figure S4: (a)-(h) Back gate and magnetic field mapping of the second derivative of  $R_{xx}$  with respect to B field  $(-\partial^2 R_{xx}/\partial B^2)$  at different top gate voltage, ranging from -8V to 6V with 2V step size. The temperature is 8K.

Quantum oscillations from top layer 2DEG gradually appears with increasing oscillation frequency from  $V_{tg}$  = -8 V to  $V_{tg}$  = 6 V.

# 5. Back gate dependence of top layer Landau levels



**Figure S5** Top gate voltage and magnetic field mapping of  $R_{xx}$  at different back gate voltage, (a) 20V (c) 25V (d) 30V. Top gate voltage and magnetic field mapping of the second derivative of  $R_{xx}$  with respect to top gate voltage  $(-\partial^2 R_{xx}/\partial V_{tg}^2)$  at different back gate voltage, (b) 20V (d) 25V (f) 30V. The temperature is 3K.

### 6. Total carrier density calculated from Hall measurement

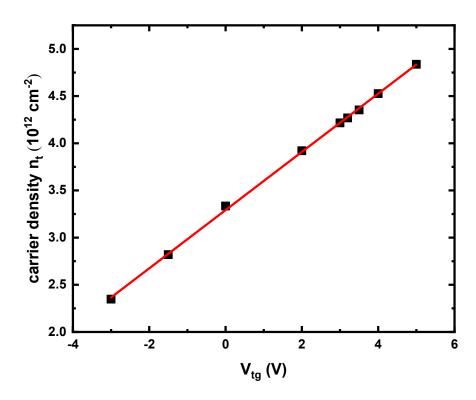
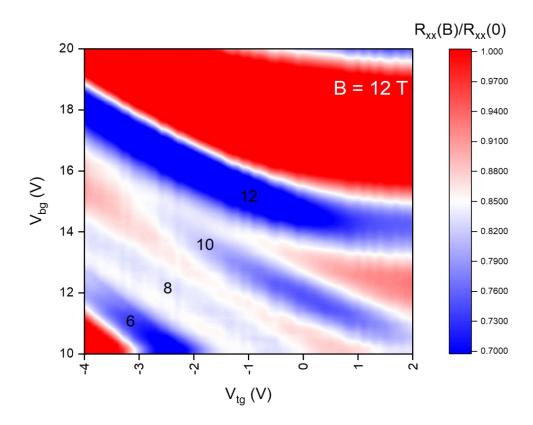


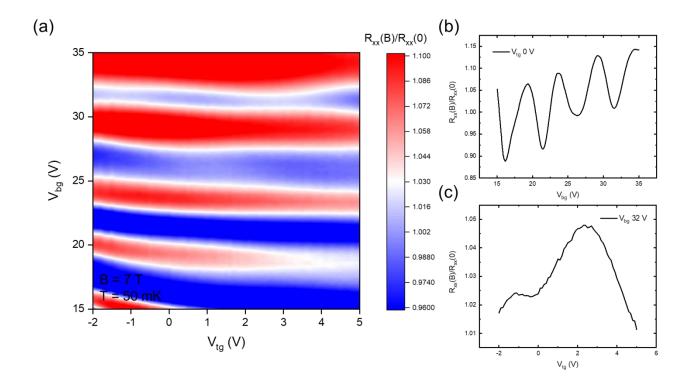
Figure S6 Total electron density (top and bottom layer) calculated from Hall data

The carrier density of the double gated Te FET at fixed  $V_{bg}$  = 10 V is calculated from Hall measurement at different  $V_{tg}$ . We use the Hall data under 5 T to avoid the influence of quantum Hall effect.

# 7. Charge transferable states at higher filling factors



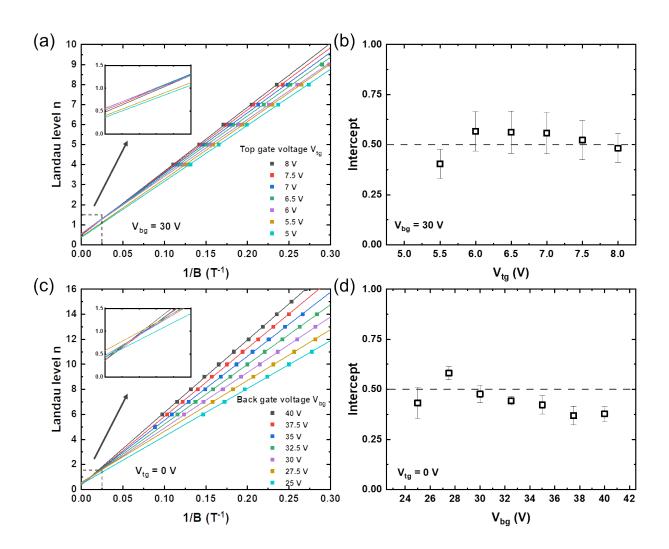
**Figure S7** Color mapping of  $R_{xx}$  by changing both top and back gate voltage at the magnetic field of 12 T. The Landau levels (filling factor 6, 8, 10 and 12) are controlled by both top and back gate voltage.



**Figure S8** (a) Color mapping of  $R_{xx}$  by changing both top and back gate voltage at the magnetic field of 7 T. (b) Bottom layer quantum oscillation at  $V_{tg} = 0$  V. (c) Top layer quantum oscillation at  $V_{bg} = 32$  V.

Figure S7 shows the color mapping of  $R_{xx}$  in another similar double-gated 2D Te device with the thickness around 20 nm. The continues quantum Hall states of filling factor 6, 8, 10 and 12 indicate the charge transferable states in 2D Te wide quantum wells. Figure S8 show the quantum oscillations at the magnetic field of 7 T. Two sets of quantum oscillations originated from top and bottom layer 2DEG are identified.

# 8. Topological non-trivial $\pi$ Berry phase in quantum Hall sequences in both top and bottom layer electrons.



**Figure S9** (a) Landau fan diagram under different top gate voltages  $V_{tg}$ . The back gate voltage is fixed at 30 V. Inset: magnified view of grey dashed box in (a) with linear fittings extrapolated to the y axis. (b) Intercept of linear fitting versus top gate voltages. The grey dashed line corresponds to the  $\pi$  Berry phase. (c) Landau fan diagram under different back gate voltages  $V_{bg}$ . (d) Intercept of linear fitting versus back gate voltages. The minima in quantum oscillations are assigned to integer Landau level n.

The top layer quantum oscillations can be extracted from the mapping of the  $R_{xx}$  by sweeping both the magnetic field B and the top gate voltage  $V_{tg}$ . The threefold screw symmetry of the Tellurium crystal protected the Weyl node at the edge of the conduction band<sup>1,2</sup>. Because of the Weyl node at H point, the cyclotron picks up a  $\pi$  Berry phase in the quantum Hall sequences.

In Figure S9, we extracted the quantum oscillations from both top and bottom layer 2DEG. We assigned the integer Landau level n to the minima of the quantum oscillations. The 0.5 intercept in Landau fan diagram (top layer Figure S9(a and b), back layer Figure S9(c and d)) indicates the  $\pi$  Berry phase caused by the Weyl fermions.

#### References

- (1) Qiu, G.; Niu, C.; Wang, Y.; Si, M.; Zhang, Z.; Wu, W.; Ye, P. D. Quantum Hall Effect of Weyl Fermions in N-Type Semiconducting Tellurene. *Nat. Nanotechnol.* **2020**, *15* (7), 585–591.
- (2) Hirayama, M.; Okugawa, R.; Ishibashi, S.; Murakami, S.; Miyake, T. Weyl Node and Spin Texture in Trigonal Tellurium and Selenium. *Phys. Rev. Lett.* **2015**, *114* (20), 206401.